

FORM PTO-1449	Atty. Docket No.: I69.12-0556	Application No.: 10/674,173
LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT	First Named Inventor: Kalman Pelhos et al.	
	Filing Date: Herewith	Group Art: 1773

U.S. PATENT DOCUMENTS

Examiner Initial	Document No.	Date	Name	Class	Sub Class	Filing Date If Appropriate	
HLL	AA	4,395,439	07/26/83	Kitamoto et al.	427	132	05/19/81
HLL	AB	4,426,265	01/17/84	Brunsch et al.	204	192 M	02/26/82
HLL	AC	4,950,548	08/21/90	Furusawa et al.	428	611	05/23/89

FOREIGN PATENT DOCUMENTS

Document No.	Date	Country	Class	Sub Class	Translation Yes No

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

HLL	AD	Eiji Kita, Kimiteru Tagawa, Masafumi Kamikubota and Akira Tasaki; Magnetic recording media prepared by oblique incidence; November 1981; IEEE Transactions on Magnetics, Vol. Mag-17, No. 6
HLL	AE	R. Sugita, N. Echigo, K. Tohma and C. Yamamitsu; Incident angle dependence of recording characteristics of vacuum deposited Co-Cr Films; September 1990; IEEE Transactions on Magnetics, Vol., 26, No. 5
HLL	AF	J.P.C. Bernards, G.J.P. van Engelen, C.P.G. Schrauwen, H.A.J. Cramer, S.B. Luitjens; Simulation of the recording process with a VSM on Co-Cr and Co-Ni-O layers deposited at oblique incidence; September 1990; IEEE Transactions on Magnetics, Vol., 26, No. 5
HLL	AG	Ki-Seok Moon and Sung-Chul Shin; Dependence of structural and magnetic properties on deposition angle in electron-beam evaporated Co/Pt multilayer thin films; 1996; American Institute of Physics
HLL	AH	Yung-Chieh Hsieh and Sergei Gadetsky; Takao Suzuki; M. Mansuripur; Oblique sputtering of amorphous TbFeCo thin films on glass substrates and the effect of deposition angle on perpendicular magnetic anisotropy; 1997; American Institute of Physics
HLL	AI	R. D. McMichael; C. G. Lee; J. E. Bonevich, P. J. Chen, W. Miller, and W. F. Egelhoff, Jr.; Strong anisotropy in thin magnetic films deposited on obliquely sputtered Ta underlayers; November 1, 2000; Journal of Applied Physics Volume 88, Number 9
HLL	AJ	M.J. Hadley, R. Atkinson, R.J. Pollard; Magnetic properties of Co films deposited onto obliquely sputtered Ta underlayers; 2002; Elsevier Science B.V.

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DATE CONSIDERED:

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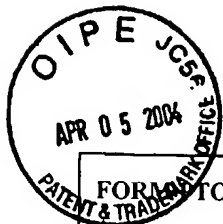
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

HK	AK	M. Cartier, S. Auffret, P. Bayle-Guillemaud, F. Ernult, F. Fetta, and B. Dieny; Influence of deposition angle on the properties of NiO spin-valves; February 1, 2002; American Institute of Physics
HK	AL	U. F. Zheng and J. P. Wang; Control of the tilted orientation of CoCrPt/Ti thin film media by collimated sputtering; May 15, 2002; American Institute of Physics
HK	AM	A. Lisfi, J. C. Lodder, H. Wormeester, and B. Poelsema; Reorientation of magnetic anisotropy in obliquely sputtered metallic thin films; 2002; The American Physical Society Physical Review B 66, 174420 (2002)
HK	AN	Anup G. Roy and David E. Laughlin; Effect of seed layers in improving the crystallographic texture of CoCrPt perpendicular recording media; May 15, 2002; Journal of Applied Physics; Volume 91, Number 10

EXAMINER: H. Uith

DATE CONSIDERED: 10/24/04

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FORM TO-1449	Atty. Docket No.: 169.12-0556	Application No.: 10/674,173
LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT	First Named Inventor: Kalman Pelhos	
	Filing Date: September 29, 2003	Group Art: 2652 1773

U.S. PATENT DOCUMENTS

Examiner Initials	Document No.	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Documents
AA			
AB			

FOREIGN PATENT DOCUMENTS

		Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Documents	Translation Yes No
HA	AC	WO8007250	06-14-1994	Hitachi Ltd	No
HA	AD	2002042326	07-19-00	KYOCERA CORP	Yes

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

HA	AE	Kiwamu Tanahashi, Yuzuru Hosoe, Masaaki Futamoto; <i>Magnetic Anisotropy and Microstructure of Obliquely Evaporated Co/Cr Thin Films</i> ; July 24, 1995; pgs. 265 - 272.
HA	AF	Y.F. Zheng and J.P. Wang; <i>Control of the Tilted Orientation of CoCrPt/Ti thin film media by collimated sputtering</i> ; May 15, 2002; V931 pgs. 0007 - 0009.
HA	AG	M.J. Hadley, R. Atkinson, R.J. Pollard; <i>Magnetic Properties of Co Films Deposited Onto Obliquely Sputtered Ta Underlayers</i> ; January 31, 2002.
HA	AH	Dieter Weller and Andreas Moser; <i>Thermal Effect Limits in Ultrahigh-Density Magnetic Recording</i> ; November 1999; volume 35, pgs. 4423 - 4439.
HA	AI	R.D. McMichael, C.G. Lee, J.E. Bonevich, P.J. Chen, W. Miller, and W.F. Egelhoff, Jr; <i>Strong Anisotropy in Thin Magnetic Films Deposited on Obliquely Sputtered Ta Underlayers</i> ; volume 88, No. 9, pgs. 5296 - 5299.0
HA	AJ	A. Hagemeyer, H.J. Richter, H. Hibst, V. Maier and L. Marosi; <i>Crystallographic Texture and Morphology of Obliquely Deposited Co-Cr Magnetic Thin Films on Flexible Polymeric Substrates</i> ; August, 10, 1993; pgs. 199 - 202.
HA	AK	T. Hikosaka, Y. Tamaka, T. Sonoda, and R. Nishikawa; <i>Cr Underlayer's Effect on the Magnetic and Crystalline Properties of Co Alloy Film</i> ; June 1988; volume 3, No. 6, pgs. 423 - 424.
HA	AL	J.C. Lodder; <i>Magnetic Thin Films for High-Density Recording</i> ; 1996; pgs 474 -483

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DATE CONSIDERED: 10/29/04

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